

Electronic Acknowledgement Receipt

EFS ID:	1255417
Application Number:	10695374
International Application Number:	
Confirmation Number:	5323
Title of Invention:	Process for removing impurities from low dielectric constant films disposed on semiconductor devices
First Named Inventor/Applicant Name:	Mark S. Chace
Customer Number:	23389
Filer:	Steven Fischman/Grace Colucci
Filer Authorized By:	Steven Fischman
Attorney Docket Number:	FIS920030172US1
Receipt Date:	16-OCT-2006
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Application Type:	Utility

Payment information:

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File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part /.zip	Pages (if appl.)
1		FIS920030172US1_RESP_FOA.pdf	490073	yes	19

Multipart Description/PDF files in .zip description		
Document Description	Start	End
Transmittal letter	1	3
Claims	4	9
Amendment After Final	10	19

Warnings:

Information:

Total Files Size (in bytes):	490073
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New Applications Under 35 U.S.C. 111
If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.

National Stage of an International Application under 35 U.S.C. 371
If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.